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PATENT APPLICATION
10/696,326

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	Xun Zhang, et al.
Serial No.:	10/696,326
Date Filed:	October 29, 2003
Group Art Unit:	1756
Examiner:	Rosasco, Stephen D.
Title:	PHOTOMASK ASSEMBLY AND METHOD FOR PROTECTING THE SAME FROM CONTAMINANTS GENERATED DURING A LITHOGRAPHY PROCESS

MAIL STOP – AMENDMENT
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

I hereby certify that this correspondence is being deposited with the United States Postal Service as Express Mail No. EV628933817US addressed to: Mail Stop - Amendment, Commissioner of Patents, Office, P.O. Box 1450, Alexandria, VA 22313-1450, on September 2, 2005.


Jason Lee Ivey

Dear Sir:

RESPONSE TO OFFICE ACTION

In response to the Office Action mailed June 2, 2005, Applicants respectfully submit the following remarks set forth below and request favorable action thereon.

Although the claims have not been amended, a **Listing of the Claims** for the Examiner's convenience begins on page 2 of this paper.

Remarks/Arguments begin on page 9 of this paper.